

巨玻固能(苏州)薄膜材料有限公司 Jubo Guneng(SuZhou)Thin Film Materials Co., Ltd.

Material材料名称:	HfO2 氧化铪
Article No.产品编码:	BoSE-07-01
Delivery Form产品规格:	1.0-4.0mm 4N Black
Material Properties:	Chemical Formula分子式: HfO2
材料特征:	Purity纯度: (HfO2+Zr) >4N Zr<0.1%
	Typical Impurities杂质类型 [ppm]: Al<60 Si<30 Ca,Fe,Ni,Ti,Mg,Cu,Mn,Cr<10
	Density-theoretical 理论密度: 9.7 g/cm3
	Melting Point熔点: 2812 °C
Test Parameters:	Coating Equipment镀膜设备: ZZS 700
测试参数:	Evaporation Source蒸发源: Electron Beam Gun/Mo Boat/Ta Boat 电子枪/钼舟
	Substrate Temp.基底温度: 100°C ~ 300 °C
	Process Gas充气压力: 1~2 x 10 ⁻⁴ mbar Oxygen
	Evaporation Rate蒸发速率: 0.3~1.0 nm/s
Thin Film Properties:	Chemical Composition化学成分: HfO2
薄膜参数:	Refractive Index折射率: 1.9~2.07 (@550 nm)
Remark	Transparency Range透明区域: 230nm~8 μm
备注:	Melting Behaviors蒸发习性: Film densification, good at chemical stability. 成膜致密, 化学稳定性好。

Material Certification声明:

We certify, the material is in compliance with the specifications stated above.

我们证明, 该材料符合上述规范。

Date 日期: 2021-1-19
Certificate No.证书编号: JBSE-Specification 079.07.01